

A versatile tender x-ray beamline 5.3.1 for diversity R&D at the ALS

J. Feng, J. Nasiatka

Lawrence Berkeley National Laboratory, Berkeley, California 94720, USA

Introduction

BL5.3.1 was the first generation slicing beamline for ultrafast science. It has been modified and used as R&D beamline for diversity experiments from novel x-ray optics development, renewable energy research, detector calibration, protein research and chemistry research.

BL5.3.1 layout and end-stations

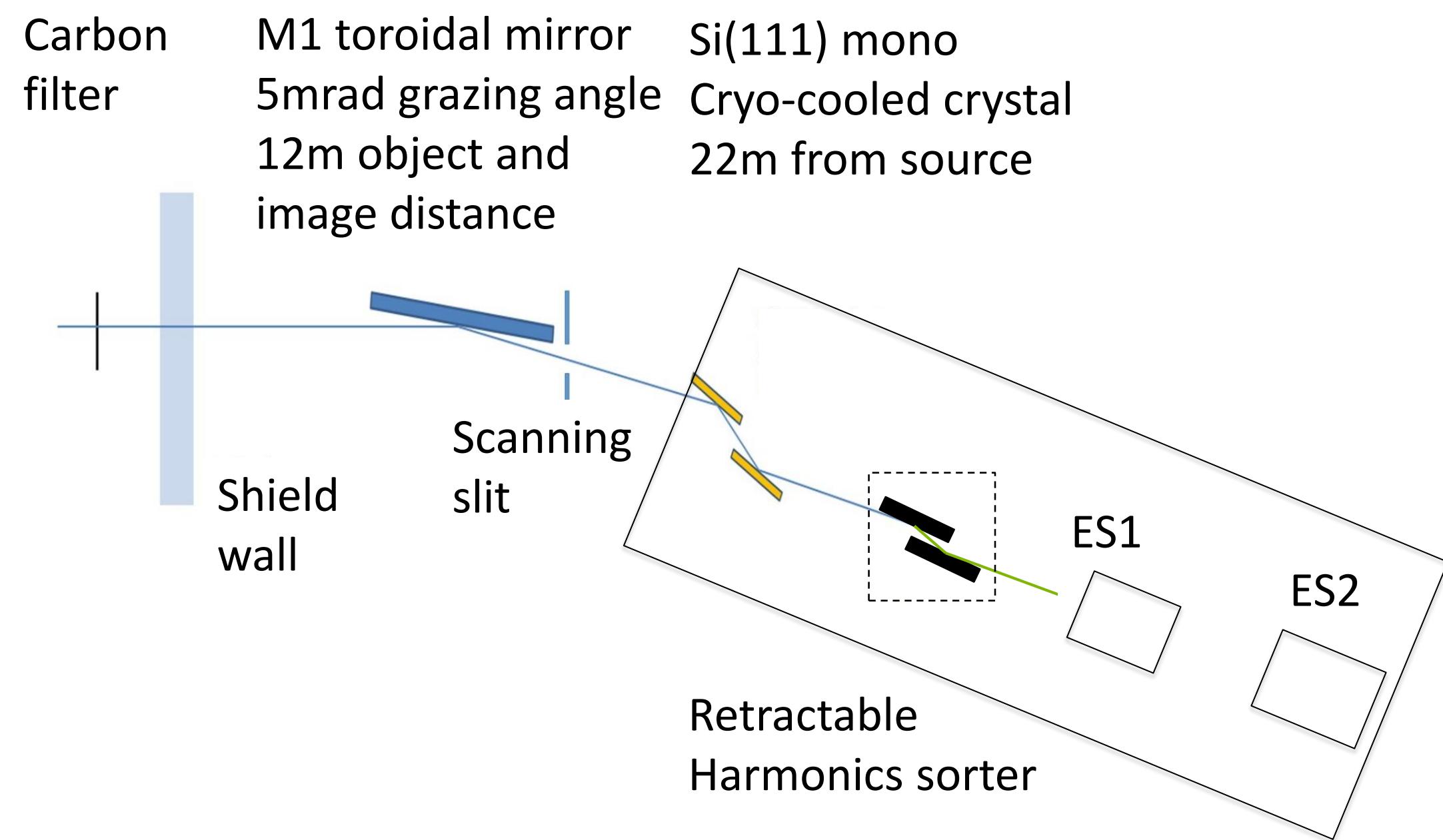


Fig. 1 Schematic of BL5.3.1 layout and end-stations

BL5.3.1 parameters

Energy range: 2.1keV-12.5keV
Focus size: typical 100umx100um
Focal distance: changeable
Flux: $\sim 3.7 \times 10^{12}$ ph/s @ 5.6keV
Energy resolution: ~ 0.8 eV@2.5keV

Note: 1. BL5.3.1 can vary beam focus and focus distance downstream.

2. BL5.3.1 can delivery both monochromatic beam and white beam.

BL5.3.1 performance measurement

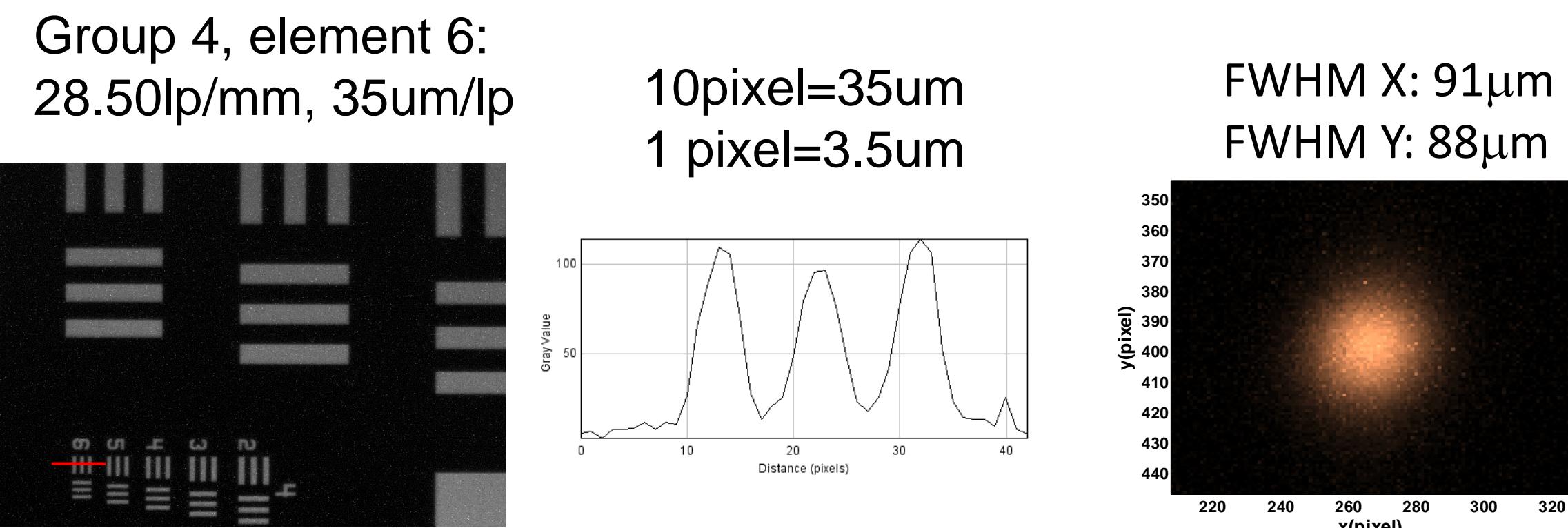


Fig. 2 BL5.3.1 measured beam size at ES1

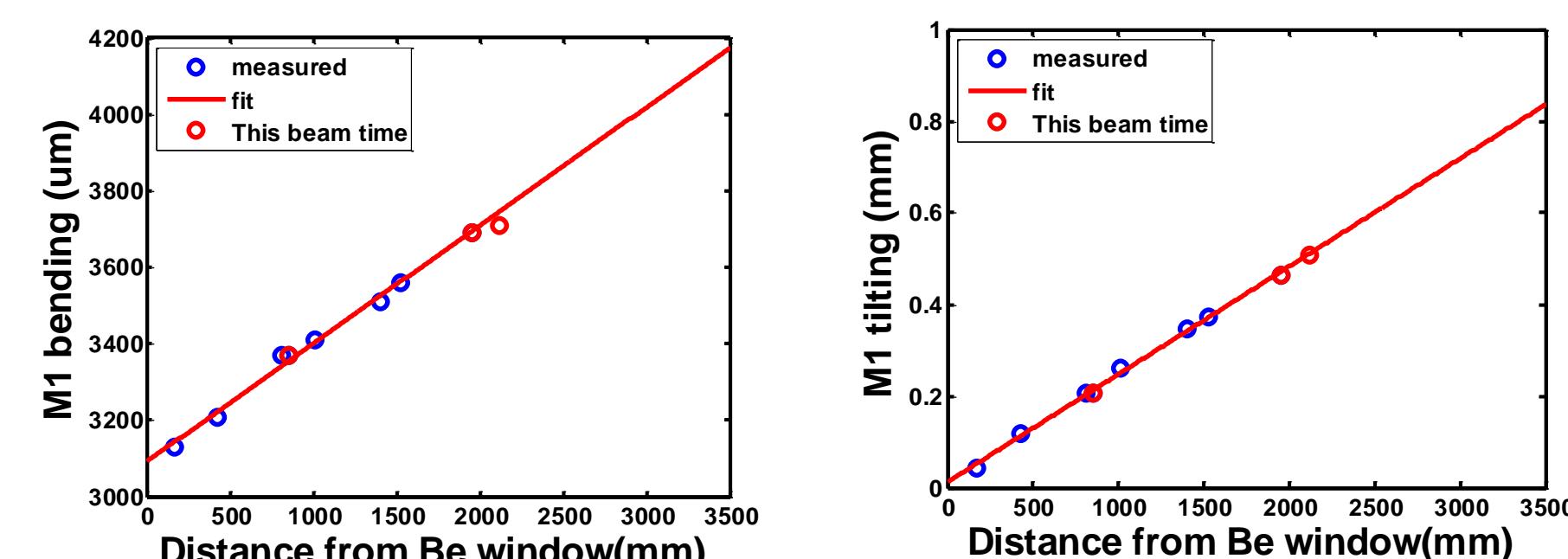
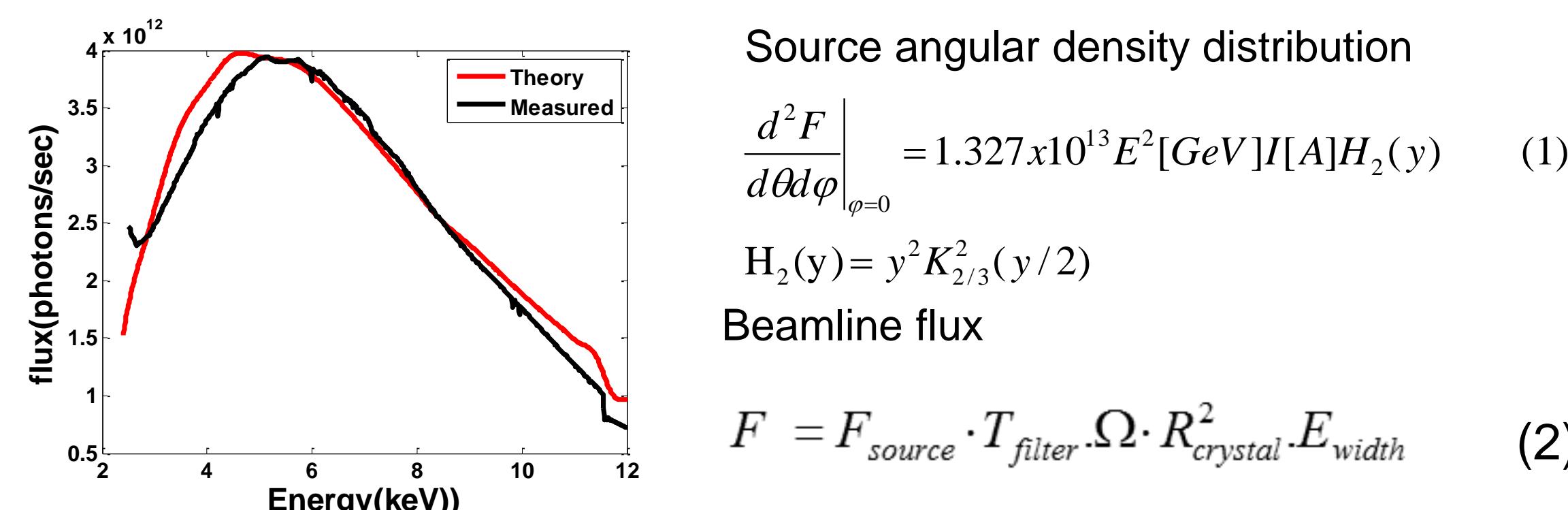


Fig. 3 BL5.3.1 measured parameters for adjustable M1 for focus beam



Source angular density distribution
 $\frac{d^2F}{d\theta d\varphi}|_{\varphi=0} = 1.327 \times 10^{13} E^2 [\text{GeV}] I[\text{A}] H_2(y) \quad (1)$
 $H_2(y) = y^2 K_{2/3}^2(y/2)$
Beamline flux

$$F = F_{\text{source}} \cdot T_{\text{filter}} \cdot \Omega \cdot R_{\text{crystal}}^2 \cdot E_{\text{width}} \quad (2)$$

Fig. 4 BL5.3.1 measured flux and comparison with calculation

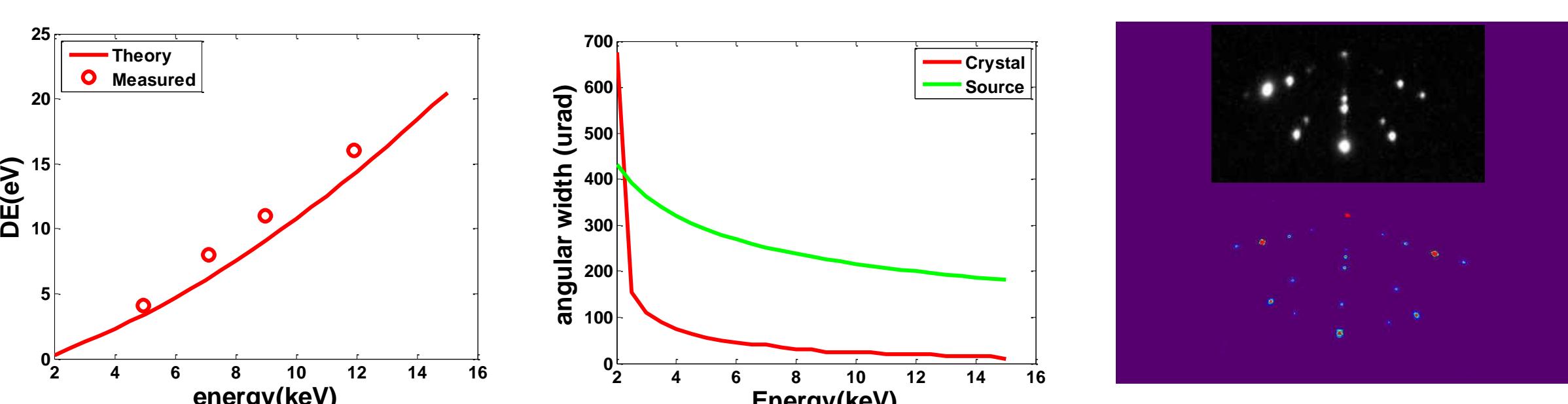


Fig. 5 BL5.3.1 energy resolving power and diffraction pattern from mono

Two mirror harmonics suppressor at BL5.3.1

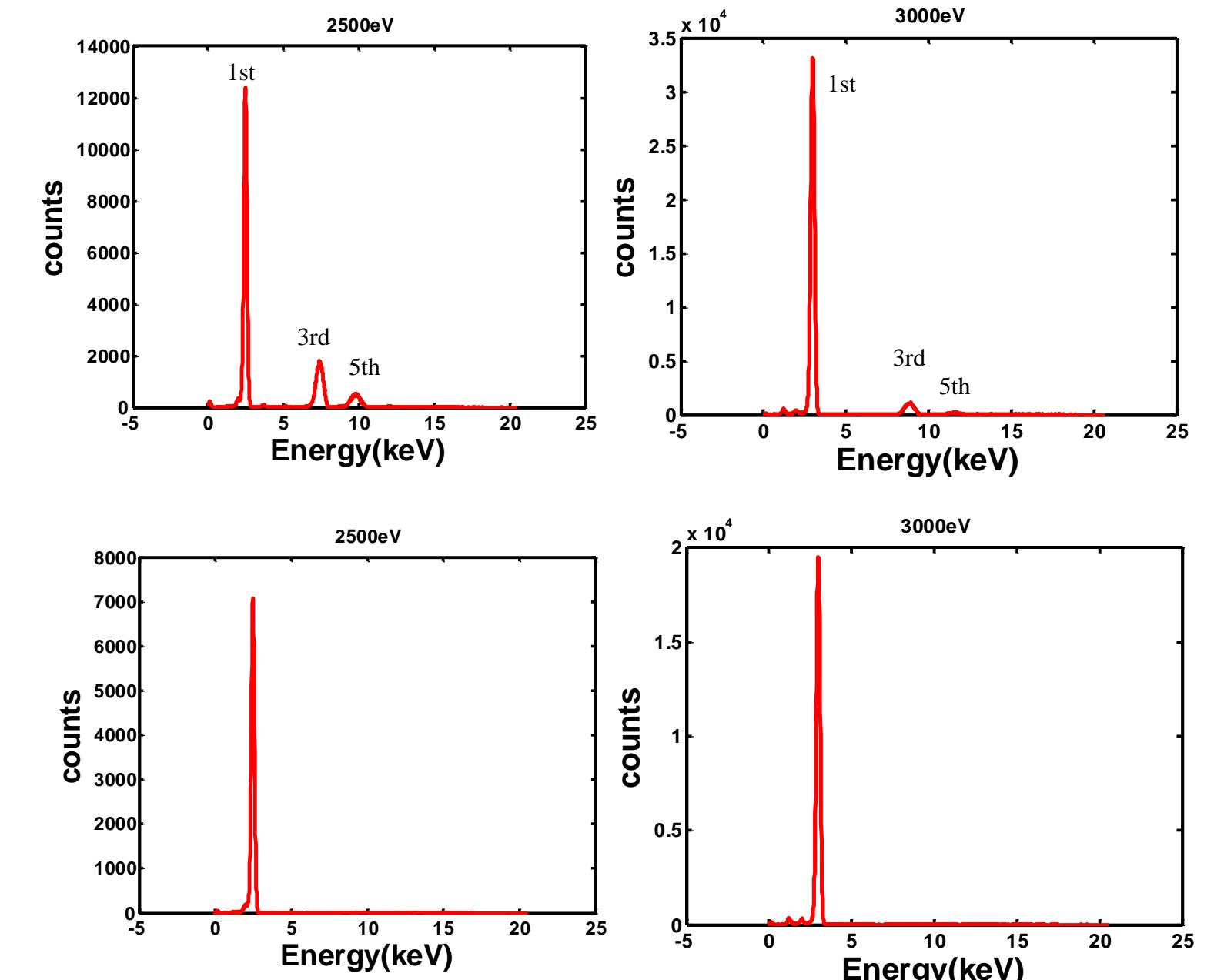


Fig. 6 measured harmonics suppressing efficiency with a suppressing ration $>10^4$

On-going projects at BL5.3.1

- Advanced x-ray adaptive Optics R&D for ALS-U and future light source. PI: Lisa A. Poyneer, LLNL, LDRD
- High QE structured photocathode R&D for detector, PI: Y.Opacich, National Security Technologies, LLC, LDRD
- White beam x-ray protein footprinting, PI: S.Gupta, C.Ralston, LBNL
- Novel Li-S battery cell research, PI: J.H.Guo, LBNL
- High resolution RIXS measurement of UO₂, PI: D.Shu, LBNL
- TReXS, A.Hexemer
- EXAFS, X-ray diffraction for magnetism materials, F.Javier Palomars, CSIC, Spain

Contact information

Jun Feng, fjun@lbl.gov, Tel: 510-495-2471